

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	50	("5683971" "5746234" "5927305" "4316666" "6118511" "4434067" "4544446" "5339842" "5357687" "5413810" "5443785" "5456759" "5569330" "5601655" "5606251" "5695833" "5715612" "5727332" "5737673" "5745946" "5749159" "5752532" "5772784" "5775827" "5802436" "5830805" "5829156" "5834148" "5868862" "5868856" "5868150" "5878760"	USPAT	2003/08/11 14:04	
2	BRS	L5	4	maeda-norio.in.	USPAT	2003/08/11 14:16	
3	BRS	L6	13	sumi-koji.in.	USPAT	2003/08/11 14:17	
4	BRS	L8	1	oono-masao.in.	USPAT	2003/08/11 14:18	
5	BRS	L9	0	tani-naoaki-izu.in.	USPAT	2003/08/11 14:18	
6	BRS	L10	0	tani-naoaki-\$.in.	USPAT	2003/08/11 14:19	
7	BRS	L11	13	tani-naoaki.in.	USPAT	2003/08/11 14:19	
8	BRS	L12	25455	(substrate\$1 of semiconductor\$1 or wafer\$1) near6 (drier or dry\$3)	USPAT	2003/08/11 14:24	
9	BRS	L13	118	12 and ((clean\$3 near2 fluid) near5 (substrate\$1 or wafer\$1 or semiconductor\$1))	USPAT	2003/08/11 14:25	
10	BRS	L14	16	13 and ((dry\$3 near2 fluid) near5 (substrate\$1 or wafer\$1 or semiconductor\$1))	USPAT	2003/08/11 14:25	
11	BRS	L15	4	14 and ((inert near2 gas) near5 (dry\$3 near2 fluid))	USPAT	2003/08/11 14:26	
12	BRS	L16	139	12 and marangoni	USPAT	2003/08/11 14:25	
13	BRS	L17	11	16 and ((clean\$3 near2 fluid) near5 (substrate\$1 or wafer\$1 or semiconductor\$1))	USPAT	2003/08/11 14:25	
14	BRS	L18	41	16 and ((dry\$3 near2 fluid) near5 (substrate\$1 or wafer\$1 or semiconductor\$1))	USPAT	2003/08/11 14:25	
15	BRS	L19	11	18 and ((inert near2 gas) near5 (dry\$3 near2 fluid))	USPAT	2003/08/11 14:26	

	Error Definition	Errors
1		0
2		0
3		0
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11		0
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14		0
15		0

	Document ID	Issue Date	Title	Current OR	Current XRef
1	US 6495099 B1	20021217	Wet processing methods for the manufacture of electronic components	422/28	134/2; 134/3; 134/6
2	US 6460554 B2	20021008	Apparatus for rinsing and drying semiconductor wafers in a chamber with a movable side wall	134/183	134/186; 134/902
3	US 6383304 B1	20020507	Method of rinsing and drying semiconductor wafers in a chamber with a movable side wall	134/2	134/183; 134/21; 134/25.4; 134/25.5; 134/26; 134/3; 134/31
4	US 6354313 B1	20020312	Apparatus for rinsing and drying semiconductor wafers in a chamber with a movable side wall	134/183	134/186; 134/902
5	US 6348101 B1	20020219	Methods for treating objects	134/1	134/10; 134/11; 134/30; 134/31
6	US 6165277 A	20001226	Method of rinsing and drying semiconductor wafers in a chamber with a movable side wall	134/2	134/183; 134/21; 134/25.4; 134/25.5; 134/26; 134/3; 134/31; 134/902; 34/77; 34/78
7	US 6095167 A	20000801	Rinse/dry apparatus including a chamber with a moveable side wall	134/183	134/2; 134/21; 134/25.4; 134/25.5; 134/26; 134/3; 134/31; 134/902; 134/95.2; 137/395; 137/426; 137/574; 34/77; 34/78
8	US 5985041 A	19991116	Method of rinsing and drying semiconductor wafers in a chamber with a movable side wall	134/2	134/183; 134/21; 134/25.4; 134/25.5; 134/26; 134/3; 134/31; 134/902; 34/77; 34/78
9	US 5913981 A	19990622	Method of rinsing and drying semiconductor wafers in a chamber with a moveable side wall	134/3	134/183; 134/2; 134/21; 134/25.4; 134/25.5; 134/26; 134/31; 134/902; 34/77; 34/78
10	US 5749159 A	19980512	Method for precision cleaning and drying surfaces	34/426	134/10; 34/433
11	US 5715612 A	19980210	Method for precision drying surfaces	34/470	34/493

	Inventor
1	Verhaverbeke, Steven et al.
2	Florez, Barry K.
3	Florez, Barry K.
4	Florez, Barry K.
5	Walter, Alan E.
6	Florez, Barry K.
7	Florez, Barry K.
8	Florez, Barry K.
9	Florez, Barry K.
10	Schwenkler, Robert S.
11	Schwenkler, Robert S.